

REMARKS

Claims 1-11, 13-22 and 24-28 are pending in the present application. Claims 12 and 23 have been cancelled, and no claims have been added. Claims 1, 9, 19, 21, and 22 have been amended. No new matter has been added.

Claims 19-28 have been rejected under 35 U.S.C. § 112, second paragraph, as assertedly being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention. In particular, the Office Action asserted that the recitation of "the photoresist filler material" lacked an antecedent basis. In response, Applicants have amended claim 19 (and dependent claims 21 and 22) to refer to "the filler layer."

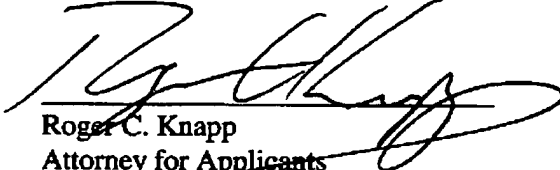
Claims 1-7 and 19-28 have been rejected under 35 U.S.C. § 102(a) as assertedly being anticipated by JP 6-302794 (hereinafter "JP '794"). Claims 9-10 and 12-17 have been rejected under 35 U.S.C. § 102(e) as assertedly being anticipated by U.S. Patent No. 5,426,058 to Nakai et al. (hereinafter "Nakai"). Claims 1-18 have been rejected under 35 U.S.C. § 102(b) as assertedly being anticipated by KR 2001-0010306 (hereinafter "KR '306"). Applicants respectfully traverse these rejections.

Claim 1 as amended recites at least one distinguishing feature that is not disclosed in the prior art, namely, the steps of "providing a wafer having a first planarization layer formed on the wafer, color filters formed over the first planarization layer, and a second planarization layer formed on the color filters in a first region and having an indentation formed therein in a second region" and "forming a layer of a filler material over the second planarization layer in the first region and over the wafer in the second region, thereby substantially filling the indentation with the filler material." Thus, Applicants' invention as recited in claim 1 forms a layer of a filler material, which substantially fills the indentation, over the second planarization layer. Independent claims 9 and 19 have been amended to include a similar limitation. In contrast, none of the references (JP '794, Nakai, and KR '306) show this feature.

In view of the above, Applicants respectfully submit that the application is in condition for allowance and request that the Examiner pass the case to issuance. If the Examiner should have any questions, Applicants request that the Examiner contact Applicants' attorney at the address below. No fee is believed due in connection with this filing. However, in the event that there are any fees due, please charge the same, or credit any overpayment, to Deposit Account No. 50-1065.

Respectfully submitted,

September 20, 2004
Date


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